



L	Hits	Search Text	DB	Time stamp
Number		("5793090").PN.	USPAT;	2004/02/06
1	1	(*5/95050). [4.	US-PGPUB	19:47
		("6391731").PN.	USPAT:	2004/02/06
2	,	("6)91/31").] IV.		
		(n (n) - 2 (n) PA	US-PGPUB	19:46
3	1	("6548361").PN.	USPAT:	2004/02/06
		(m	US-PGPUB	19:47
4	1	("5529951").PN.	USPAT;	2004/02/06
		// \\ \\ \\ \\ \\ \\ \\ \\ \\ \\ \\ \\ \	US-PGPUB	19:47
5	4	· (("5793090").PN.) or (("6391731").PN.) or	USPAT;	2004/02/06
		(("6548361").PN.) or (("5529951").PN.)	US-PGPUB	20:00
6	1	("20020098689").PN.	USPAT;	2004/02/06
			US-PGPUB	20:00
7	70989	Ge or germanium	USPAT;	2004/02/06
			US-PGPUB	20:00
8	i	(("20020098689").PN.) and (Ge or germanium)	USPAT:	2004/02/06
			US-PGPUB	20:19
9	11918	LPCVD	USPAT;	2004/02/06
			US-PGPUB	20:21
10	i	("6548361").PN.	USPAT;	2004/02/06
			US-PGPUB	20:20
11	0	LPCVD and (("6548361").PN.)	USPAT;	2004/02/06
			US-PGPUB	20:20
12	i	(("20020098689").PN.) and LPCVD	USPAT;	2004/02/06
	}		US-PGPUB	20:20
13	14054	LPCVD or "low pressure chemical vapor deposition"	USPAT;	2004/02/06
			US-PGPUB	20:21
14	0	(("6548361").PN.) and (LPCVD or "low pressure	USPAT:	2004/02/06
		chemical vapor deposition")	US-PGPUB	20:21
15	1	(("20020098689").PN.) and (LPCVD or "low	USPAT:	2004/02/06
		pressure chemical vapor deposition")	US-PGPUB	20:37
16	+35522	oxygen or silane	USPAT:	2004/02/06
			US-PGPUB	20:37
17	0	(("20020098689").PN.) and (oxygen or silane)	USPAT:	2004/02/06
,			US-PGPUB	20:37
18	915453	0	USPAT;	2004/02/06
	,,,,,,		US-PGPUB	20:38
19	1	(("20020098689").PN.) and ()	USPAT;	2004/02/06
.,		W ====================================	US-PGPUB	20:43
20	,	(("6391731").PN.) and (LPCVD or "low pressure	USPAT;	2004/02/06
20		chemical vapor deposition")	US-PGPUB	20:45
7.1		(("5793090").PN.) and (LPCVD or "low pressure	USPAT;	2004/02/06
21		chemical vapor deposition")	US-PGPUB	20:46
22		, ,		2004/02/06
22	2	(("6656749") or ("6426278")).PN.	USPAT;	
			US-PGPUB	20:46

23	1	(LPCVD or "low pressure chemical vapor deposition")	USPAT;	2004/02/06
		and ((("6656749") or ("6426278")).PN.)	US-PGPUB	20:48
24	1505	(LPCVD or "low pressure chemical vapor deposition")	USPAT:	2004/02/06
		with (oxygen or silane)	US-PGPUB	20:52
2.5	96331	"CVD" or "chemical vapor deposition"	USPAT;	2004/02/06
		, ,	US-PGPUB	20:53
26	820	((LPCVD or "low pressure chemical vapor	USPAT;	2004/02/06
		deposition") with (oxygen or silane)) with ("CVD" or	US-PGPUB	20:53
		"chemical vapor deposition")		
2.7	74345	438/\$7.ccls.	USPAT:	2004/02/06
			US-PGPUB	20:53
28	613	(((LPCVD or "low pressure chemical vapor	USPAT;	2004/02/06
		deposition") with (oxygen or silane)) with ("CVD" or	US-PGPUB	21:18
	1	"chemical vapor deposition")) and 438/\$7.ccls.		
29	4609	((438/517) or (438/522) or (438/530) or (438/660)	USPAT:	2004/02/06
		or (438/663) or (438/680) or (438/685) or	US-PGPUB	21:20
		(+38/761) or (+38/763) or (+38/785) or (+38/787)	:	
		or (438/791) or (438/923) or (438/933)).CCLS.		
30	763	(Ge or germanium) and (((438/517) or (438/522) or	USPAT;	2004/02/06
		(438/530) or (438/660) or (438/663) or (438/680)	US-PGPUB	21:20
		or (438/685) or (438/761) or (438/763) or		
		(438/785) or (438/787) or (438/791) or (438/923)		
		or (438/933)).CCLS.)		